WINSTON HSU 41526

H3 Raction

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Yi-Fan Chen,

Examiner: Huynh, Andy

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Chi-King Pu,

Shou-Kong Fan

Filing Date: 04/18/01

Art Unit: 2818

Docket No.: NAUP0280USA

Serial No.:

09/836,258

10 Title: BYPASS CIRCUITS FOR REDUCING PLASMA DAMAGE

To:

Assistant Commissioner for Patents

Washington, D.C. 20231

15 Subject: Response to the Office action dated 01/24/02

Dear Sir:

FAX COPY RECEIVED

AMENDMENT

FEB 2 2 2002

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TECHNOLOGY CENTER 2800 In response to the Office action identified above, please amend the above-identified application as follows:

In the claims:

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Cancel claims 7-14.